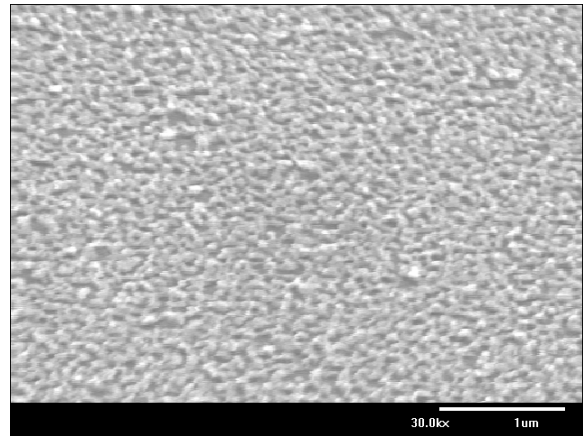
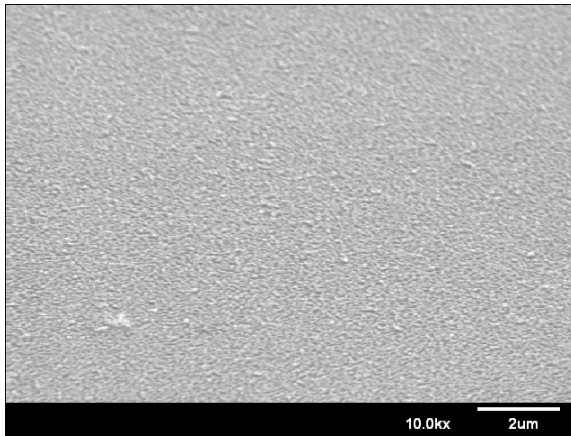
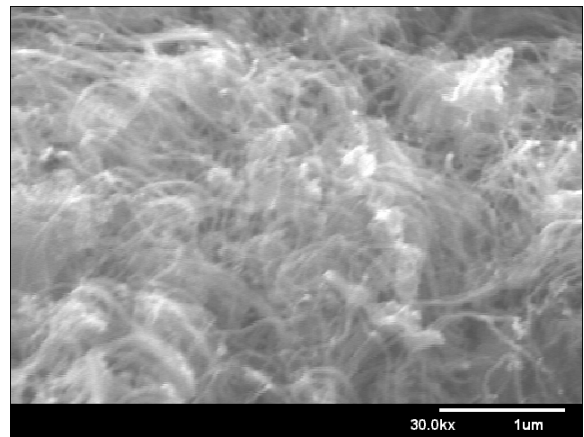
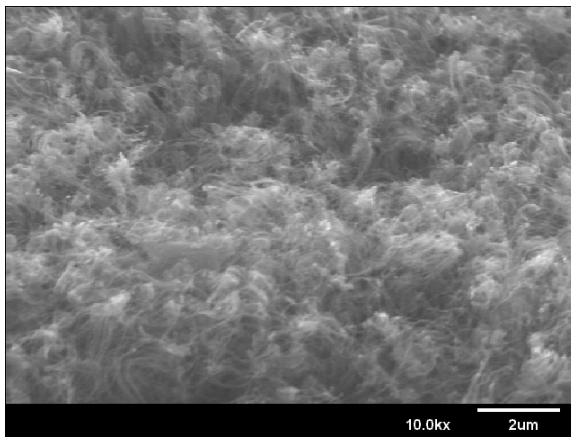


C3、550°C H₂:300 (Ni 7 nm)



C4、550°C H₂:300 (Ni 7 / TiN 20 nm)



C5、550°C H₂:300 (Ni 7 / TaN 10 nm)

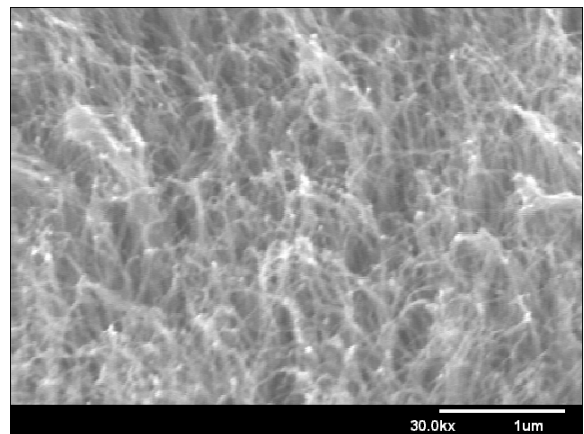
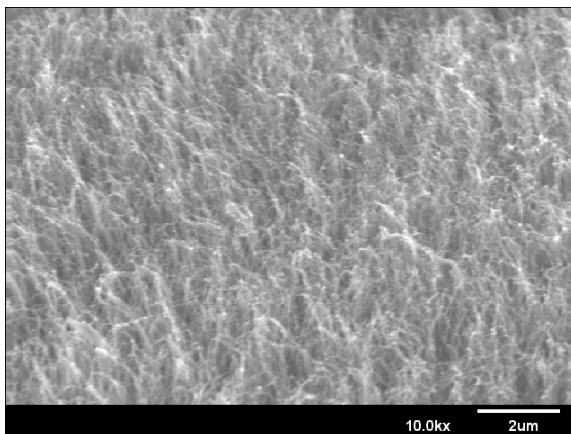


圖 4-31 製程 C 有緩衝層對照組試件(4、5) 奈米碳管 SEM 圖面(10、30 kx)

4-8 試片 TEM 圖面

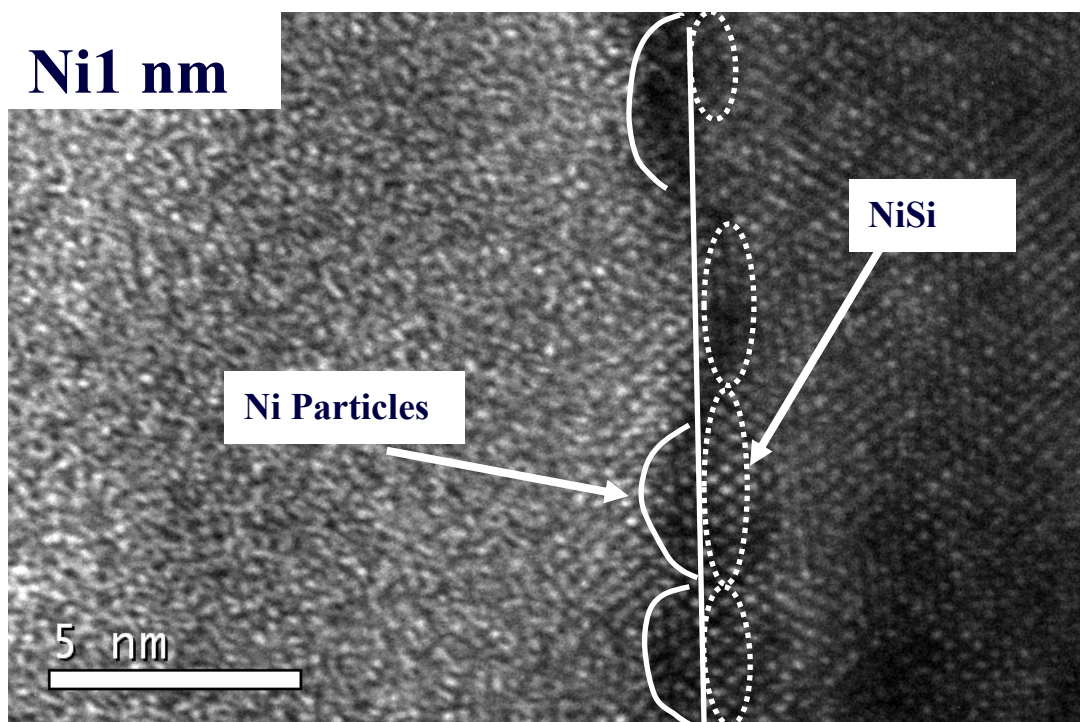


圖 4-32 試件 1(Ni1)前製程觸媒 TEM 圖面

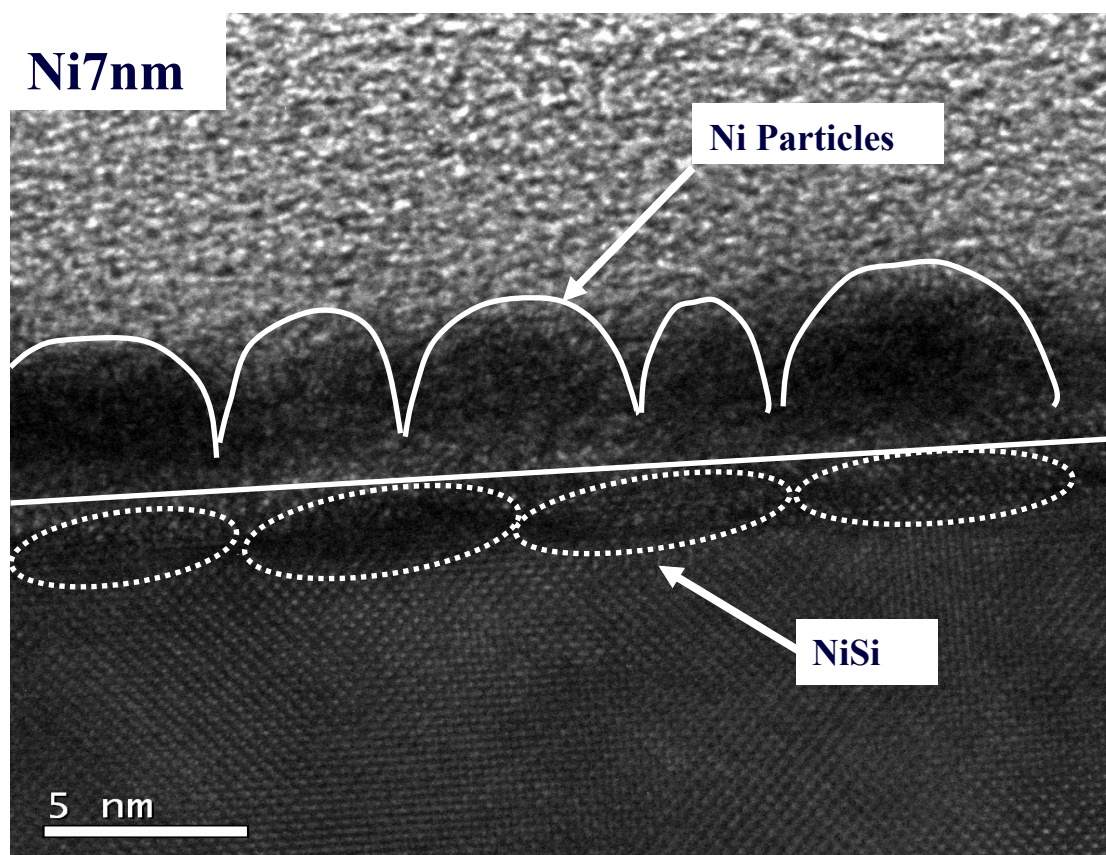


圖 4-33 試件 3 (Ni7)前製程觸媒 TEM 圖面